

Amendments to and Listing of the Claims:

Please amend claims 6 and 10 and cancel claim 8, so that the claims read as follows:

1-5. (Cancelled)

6. (Currently Amended) A method of producing a semiconductor device, comprising a step of forming a copper wiring by chemical mechanical polishing and washing with washing liquid for a semiconductor substrate comprising a ~~basic compound~~ quaternary ammonium hydroxide and mannitol.

7. (Cancelled)

8. (Cancelled)

9. (Previously Presented) The method according to claim 6, wherein the concentration of the mannitol is from 0.01 to 5 wt%.

10. (Currently Amended) The method according to claim 6, wherein the concentration of the ~~basic compound~~ quaternary ammonium hydroxide is from 0.05 to 1 wt%.